

U.S. Department of Commerce, Patent and Trademark Office				Atty Docket No.	Serial No.		
				M-12019 US	10/004,386		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				Applicants			
				George D. Papasouliotis and Robert D. Tas			
				Filing Date	Group		
				December 3, 2001	2812		
U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
CAT	AA	5,270,264	12/1993	Andideh et al.			
CAT	AB	5,227,191	7/1993	Nagashima			
CAT	AC	5,246,885	9/1993	Braren et al.			
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Foreign Patent Documents

PATENT & TRADEMARK OFFICE	Document	Date	Country	Translation			
				Class	Subclass	Yes	No

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

CAT	BG	Cote et al., "Low-Temperature Chemical Vapor Deposition Processes and Dielectric for Microelectric Circuit Manufacturing at IBM," <i>IBM Journal of Research and Development</i> , Volume 39, No. 4 (July 1995), pages 437-464.
CAT	BH	Pennington et al., "An Improved Interlevel Dielectric Process for Submicron Double-Level Metal Products," <i>Proceedings of the 6th International IEEE VLSI Multilevel Interconnection Conference</i> , (June 1989), pages 355-359.

Examiner Craig Thorp Date Considered 10/1/02

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.